



PATENT  
8017-1156

IN THE U.S. PATENT AND TRADEMARK OFFICE

In re application of

Akira USUI et al.

Conf. 8975

Application No. 10/519,571

Group 2812

Filed March 9, 2005

Examiner Elias Ullah

GROUP III NITRIDE SEMICONDUCTOR SUBSTRATE  
AND PROCESS FOR PRODUCTION THEREOF

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

MS ISSUE FEE  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In compliance with Rules 1.97 and 1.98, and in fulfillment of the duty of disclosure under Rule 1.56, the accompanying document, a copy of which is attached to this statement, is made of record on the enclosed Form PTO-1449.

A concise explanation of the relevance of this item is that this reference was cited by the Japanese Patent Office in the corresponding Japanese Application Serial No. 2002-193733, filed July 2, 2002.

Under the provisions of 37 CFR 1.97(e), the undersigned hereby certifies that each item of information contained in this Information Disclosure Statement was first cited in any communication from a foreign Patent Office in a counterpart foreign application not more than three months prior to the filing of this Statement.

Charge the \$ 1.17(p) fee of \$180 to Deposit Account  
No. 25-0120.

Respectfully submitted,

YOUNG & THOMPSON



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Robert J. Patch, Reg. No. 17,355  
745 South 23<sup>rd</sup> Street  
Arlington, VA 22202  
Telephone (703) 521-2297  
Telefax (703) 685-0573  
(703) 979-4709

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Application No.:  
**10/519,571**

Applicant:  
**Akira USUI et al.**

Filing Date:  
**March 9, 2005**

Group Art Unit:  
**2812**

(Use several sheets if necessary)

## U.S. PATENT DOCUMENTS

[illegible]

## FOREIGN PATENT DOCUMENTS

[illegible]

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**


**EXAMINER:**

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

\* English Abstract provided for the Examiner's convenience